	Application No.	Applicant(s)	
Notice of Allowability	10/648,286	HSU, SUNG-MU	
	Examiner	Art Unit	
	Chandra Chaudhari	2813 _	
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this app or other appropriate communication GHTS. This application is subject to	olication. If not include will be mailed in due	ed course. THIS
1. This communication is responsive to application filed on Au	ugust 27, 2003.		
2. ☑ The allowed claim(s) is/are <u>1-15</u> .			
3. A The drawings filed on August 27, 2003 are accepted by the	e Examiner.		
4.	been received. been received in Application No cuments have been received in this is of this communication to file a reply of this application. itted. Note the attached EXAMINER' best reason(s) why the oath or declarated be submitted. it be submitted. it on's Patent Drawing Review (PTO-1) a Amendment / Comment or in the One of the the attached of the the drawing the header according to 37 CFR 1.121(consist of BIOLOGICAL MATERIAL in the processit of BIOLOGICAL MATERIAL in the the travel of the	national stage applical complying with the recomplying attached of the state	quirements OTICE OF
 Attachment(s) 1. Notice of References Cited (PTO-892) 2. Notice of Draftperson's Patent Drawing Review (PTO-948) 3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 8-27-03 4. Examiner's Comment Regarding Requirement for Deposit of Biological Material 	5. ☐ Notice of Informal P 6. ☐ Interview Summary Paper No./Mail Dat 7. ☐ Examiner's Amendn 8. ☑ Examiner's Stateme 9. ☐ Other	(PTO-413), e nent/Comment	

The following is an examiner's statement of reasons for allowance:

The prior art does not disclose to etch the mask layer to expose portions of the first polysilicon layer, and to define a first patterned region, a second patterned region and a third patterned region, wherein the third patterned region is located between the first patterned region and the second patterned region, the exposed portions of the first polysilicon layer located in the first patterned region and the second patterned region as claimed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Chandra Chaudhari whose telephone number is 571-272-1688. The examiner can normally be reached on Mon - Fri (9:00-5:30).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Carl Whitehead Jr. can be reached on 571-272-1702. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

C. Claudhari Chandra Chaudhari September 17, 2004 Chandra Chaudhari Primary Examiner Art Unit 2813